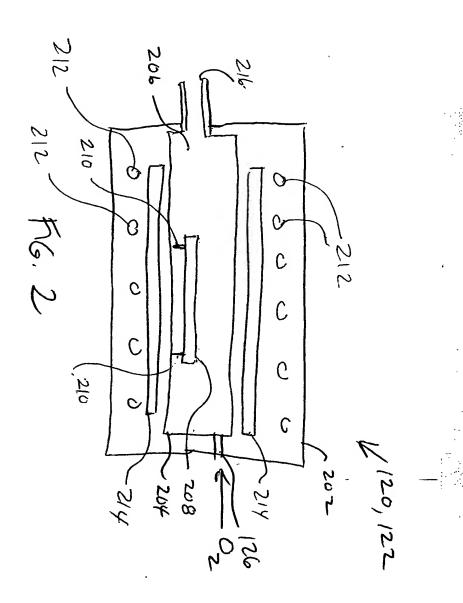


FIG. 1



V 300 PROVIDING A SUBSTRATE HAVING 5302 100 implanted alements and forming a resist mask thereon Placing SUBSTRATE INTO Processing 5304 Chamber J S306 INTRODUCETTO REPORTION GAS INTO THE PROCESSING CHAMBER TO A FIRST PARTIES PRESSURE and Changing Temperature of the Changer Kemoras BY-PRODUTS OF 5308 REMETON, IF DESIRED AMORLING SUBSTRATE TO :5310 AZTIVATE IMPLANTED ELEMENTS

MG. 3

240 PROVIDING A SUBSTRATE HAMAG A RUBIST LAKEN Former Thereon Placing THE SUBSTEAME hours, a first Temperature into THE CHAMBOR, THE CHAMBOR 5404 BEING AT A GIVEN TEMPERANRE Innoduung TO A FIRST PARDA Pressine ALLOWING THE REACTIVE GAS TO ROACT WITH SUND RESIST Newaring BY-Products of RXN Arraying of SAID SUBSTRATE 76.4